

A Novel Approach for Increased Probe Card Parallelism Utilizing Device Package Substrates



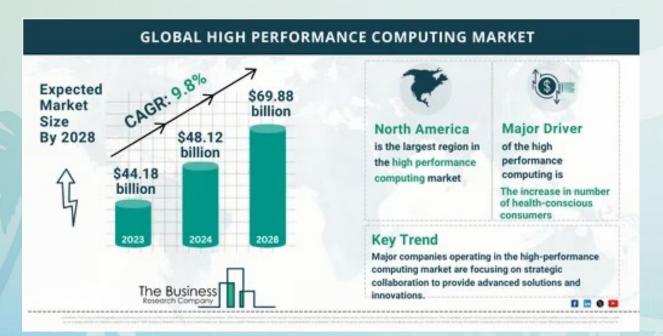
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Agenda

Motivation of Work Market Drivers Customer Challenge Development Strategy Overview Solution Approach Product Validation Results Confirmation of Solution Approach Summary and Acknowledgements

High Performance Compute (HPC) Device Market Trends

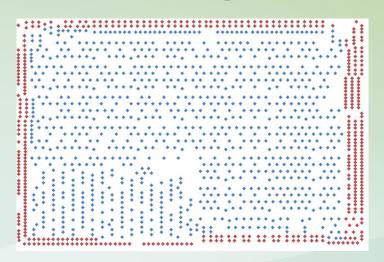
- The costs of introducing next generation devices and process technologies has exploded
 - In addition, chip design costs have increase 30x going from a 65nm design to a 3nm design
- At the same time, the market is rapidly expanding
 - CAGR: ~10% from 2023 to 2028

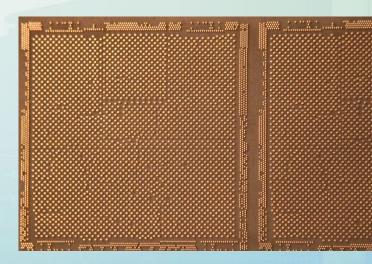




HPC Device Wafer Test Challenges

- Increased I/O and Power & Ground connections points → increase pin counts per DUT
- Critical to maintaining and improving signal fidelity to achieve entitled yields
 - Aligning SI/PI performance to device to minimize signal loss and reduce re-test rates
- Relentless drive to reduce cost of test is increasing wafer test parallelism and strategies
- Expanding test temperatures increases the thermodynamic challenges
- Probe card design strategies
 - Monolithic vs. Singulated substrates





Meeting Cost of Test Reduction Challenges – Considering Package Substrates as Space Transformer

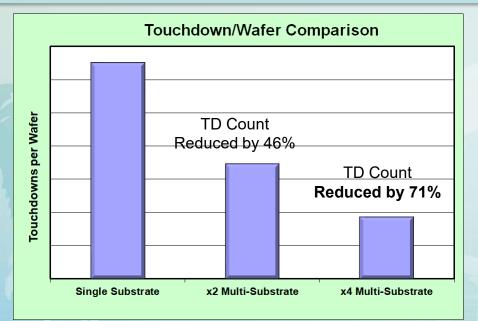
| | Advantage | Disadvantage |
|----------------------------|---|---|
| Traditional Monolithic MLO | Higher Parallelism → reduced TD count Better manufacturability Solid array is possible for lower parallelisms | Challenges to aligning SI/PI to DUT Higher MLO costs/DUT tested Slower to redesign, limited modularity |
| Package Substrate | SI/PI better aligned with DUT Built in DFT Lower substrate (MLO) costs Expect test results closely matched to end use applications | Requires skips for multi-DUT Limited parallelism for comparable monolithic area Additional manufacturing challenges |

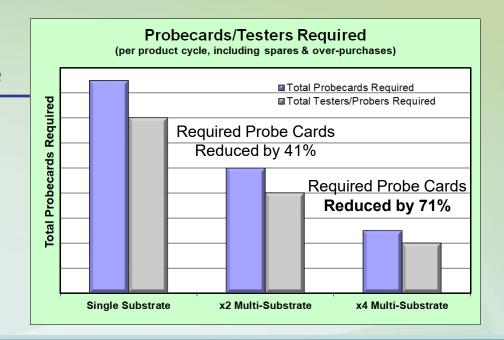
Supporting Cost of Test Reduction

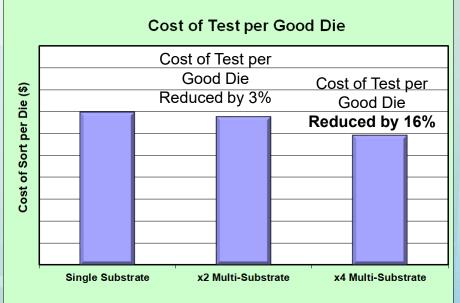
-TCOO Analysis (500 wspm): Single Substrate vs. Multi-Substrate

Objective:

- Reduce cost of test with increased parallelism
- Assumptions:
 - 300mm wafer, ~350 die, 500 wafers per month (wspm)
 - Test time, retest %, and cleaning cycle remain unchanged
 - No increase in required tester count





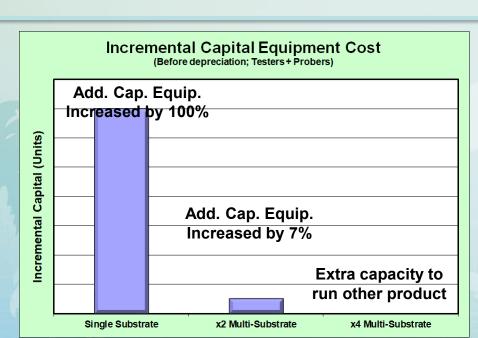


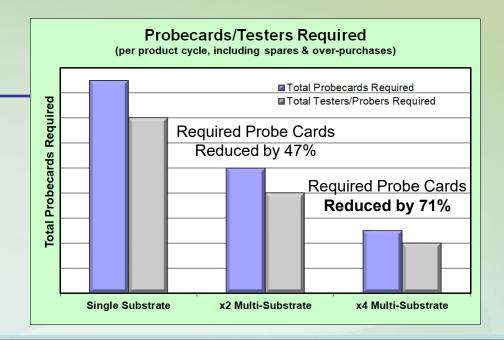
Supporting Cost of Test Reduction

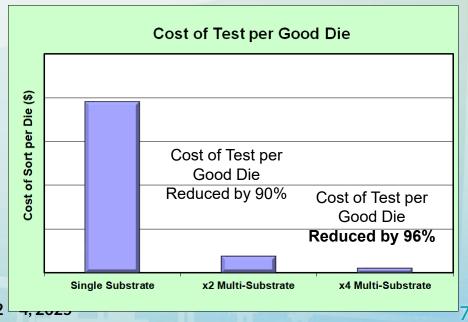
-TCOO Analysis (1,000 wspm): Single Substrate vs. Multi-Substrate

Objective:

- Reduce cost of test with increased parallelism
- Assumptions:
 - 300mm wafer, ~350 die, 1,000 wafers per month (wspm)
 - No Change to test time, retest %, and cleaning cycles
 - 14 additional testers needed to support demand







Besprozvanny/Harker 34th SWTest

34th SWTest Conference | Car sbad, CA, June 2

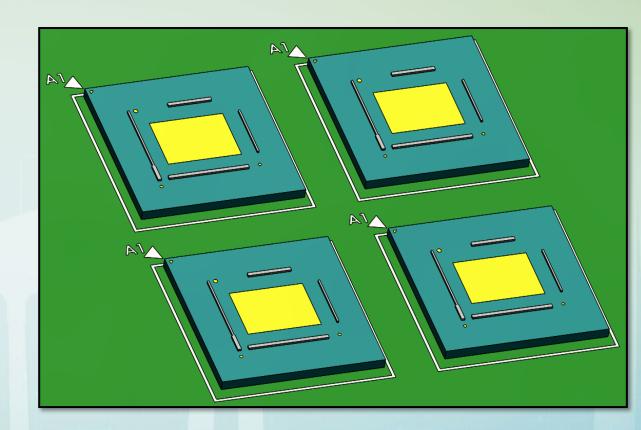
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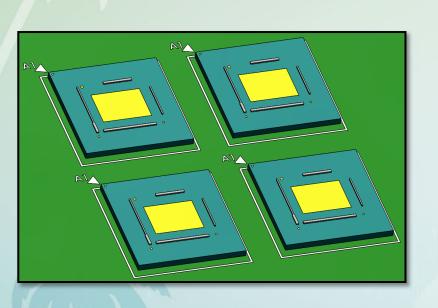
- What are the key specifications and challenges?

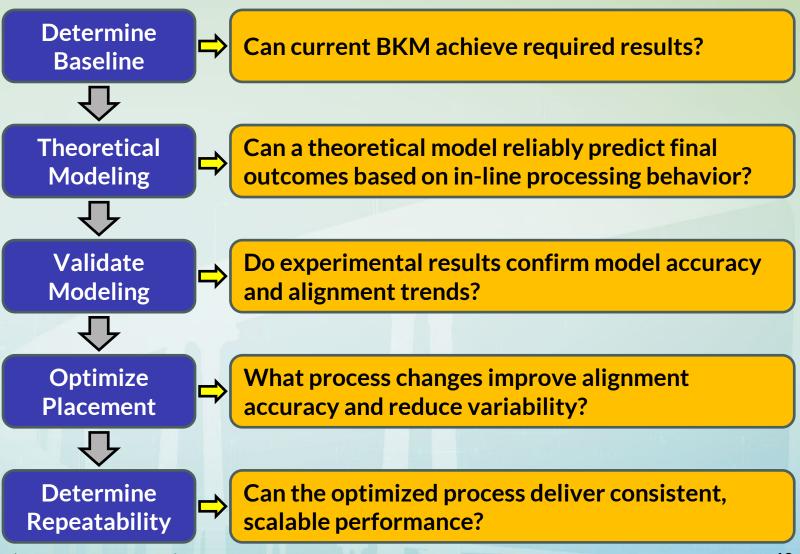
Define Criteria for HVM:

- Electrical reliability
- Multi-substrate co-alignment
- Stable assembly processing across the full temperature range.



- What is the Test-Plan?





- What defines our current baseline capabilities?

Objective:

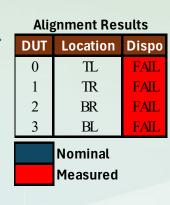
 Evaluate if current methods meet coalignment requirements

Passing Criteria:

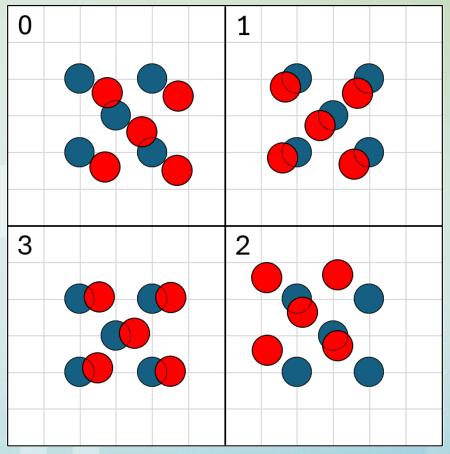
- Accurate positioning within/across substrates
- Alignment to local and global targets

Summery of Results:

- No consistent alignment between substrates
- Post-reflow results exceeded tolerance limits.



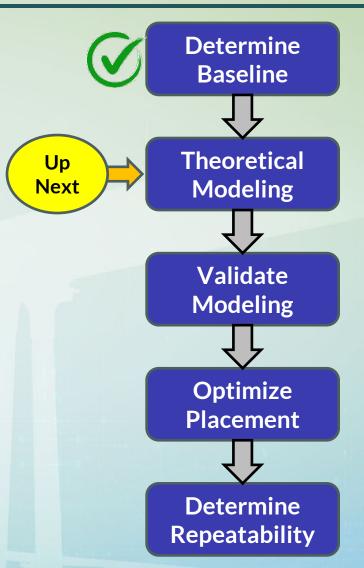
Baseline Co-alignment Results



- What are the key take-aways from BKM?

Key Take-Away:

- Current methods yield inconsistent coalignment and exceed tolerance limits.
- Alignment to local and global targets remains unreliable
- Tighter control and better placement are required for scalable, high-yield production.



- What is the criteria for the theoretical model?

Boundary Conditions:

- POR constraints limit flexibility and impact coalignment consistency
- Process variation must be managed through targeted adjustments

Control Strategy:

 Leverage controllable steps to mitigate processinduced variation and enhance repeatability

Modeling Setup:

 Build a predictive model using the proposed control strategy under optimized process conditions



- Can a theoretical model predict final substrate alignment?

Objective:

 Validate if simulations and optimized processing predict final co-alignment

Summary of Results:

 Model shows uniform radial offset beyond spec range

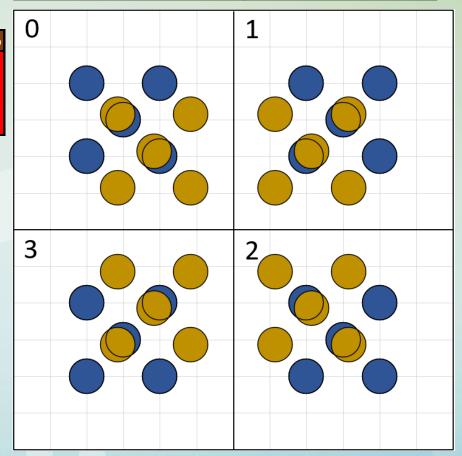
Alignment Results DUT Location Dispo 0 TL FAIL 1 TR FAIL

BR

FAIL

Nominal Theoretical

Theoretical Co-alignment Results



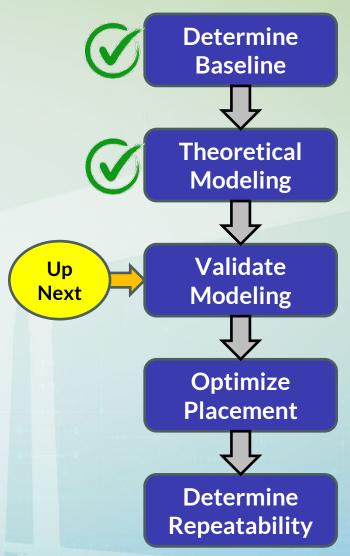
- Can we predict misalignment with thermal modeling?

Key Take-Away :

- Multi-substrate assemblies need added process control to maintain co-alignment
- Assembly process induces directional shifts that affect final alignment.

Next Steps:

- Empirically validate if the optimized control strategy accurately predicts final alignment
- Use experimental data to identify and address remaining process gaps



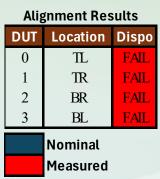
- Can a modified process approach improve co-alignment?

What is the Gameplan?

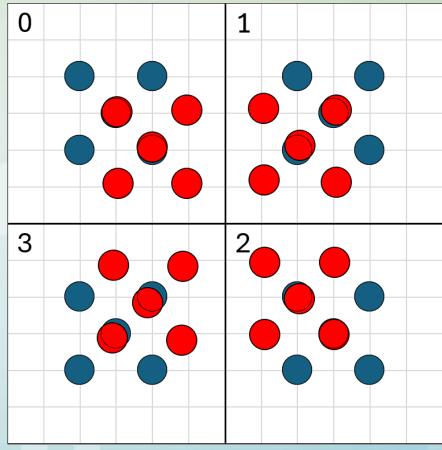
- Control key assembly factors to replicate modeled results
- Design for consistent outcomes with process control and adaptability

• Summary of Results:

- Co-alignment was repeatable
- Radial shift aligned with model predictions.



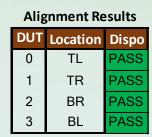
Co-alignment Results



- How well did the thermal modeling predict substrate placement?

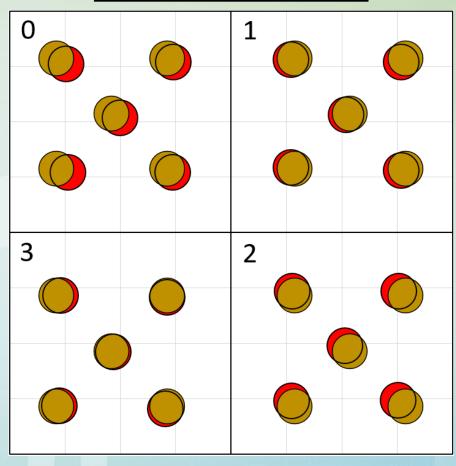
Key Take-Away:

- Simulation aligned with measured results with tolerance range.
- Model accuracy validated for realworld assemblies.





Theoretical vs. Actual



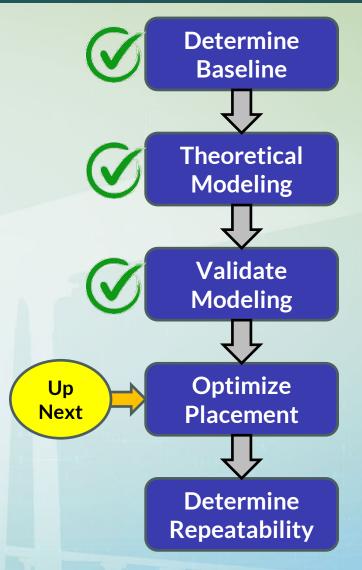
- Can we predict misalignment with thermal modeling?

Assumptions:

- In-line processing induces positional drift at final assembly.
- Empirical results confirm simulation-predicted behavior.

Next Steps:

- Refine process setup and parameters to minimize drift.
- Control positional variation.
- Improve final placement accuracy.



- Does the optimizing process setup meet co-alignment requirements?

Objective:

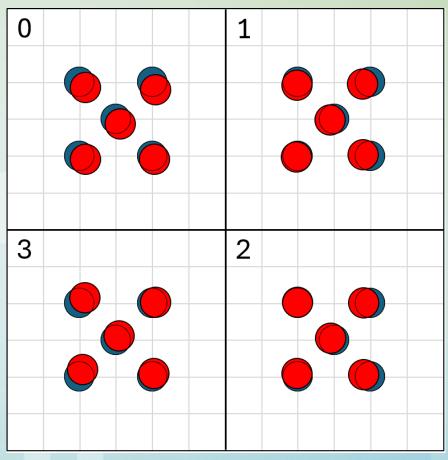
 Confirm if the optimized process produces required co-alignment results

Summary of Results:

Co-alignment at final assembly is well within spec



Co-alignment Results



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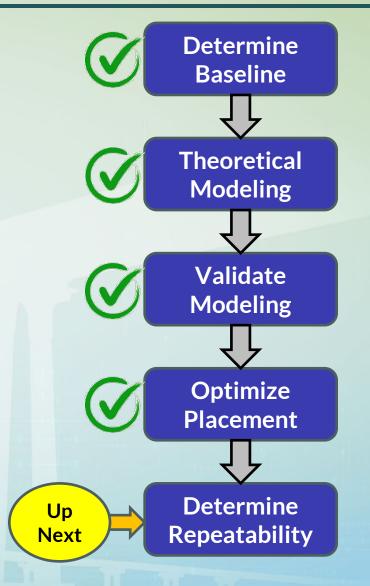
- Can we compensate misalignment with the optimized process setup?

Key Take-Away :

 Optimized setup reliably manages variation and achieves co-alignment within tolerance range.

Next Steps:

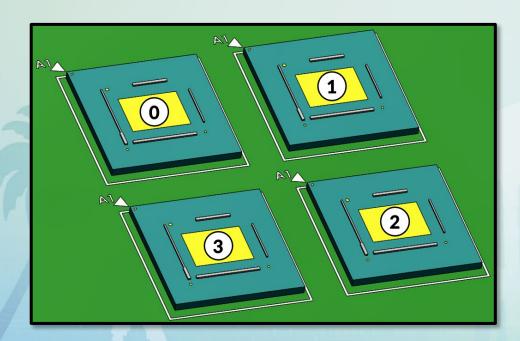
Conduct repeatability study

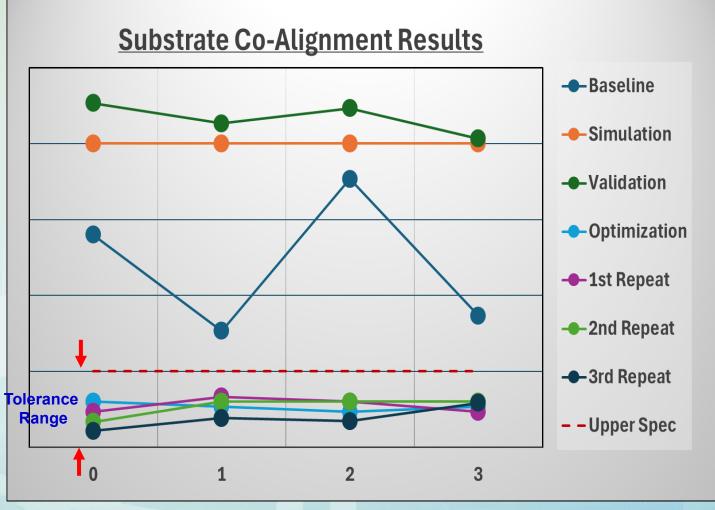


- How repeatable was the optimized solution?

Key Take-Away:

- Consistent alignment was achieved
- Stable and repeatable results.





Summary/Conclusion

Capability Assessment

- Baseline evaluation identified areas to improve process control for co-alignment
- A predictive model guided process optimization and alignment assessment
- Experimental validation confirmed the model's effectiveness for multi-substrate applications

Concept to Product

- Process refinement led to consistent, repeatable co-alignment results
- Outcome builds confidence in the updated setup for future builds

Customer Commitment

- FFI successfully delivered a validated solution on time to meet customer needs

Acknowledgements

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